

In re: Won et al.  
Serial No.: To be assigned  
Filed: Currently herewith  
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**In the Specification:**

Please replace the first paragraph under the heading "Related Application" on page 1 of the specification with the following amended paragraph:

~~This application claims the benefit of Korean Patent Application No. 1999-61337, filed December 23, 1999 and Korean Patent Application No. 2000-12056, filed March 10, 2000, the disclosures of which are hereby incorporated herein by reference.~~ This application is a divisional of Application Serial No. 09/742,647 filed on December 21, 2000, entitled "METHODS OF FORMING RUTHENIUM FILM BY CHANGING PROCESS CONDITIONS DURING CHEMICAL VAPOR DEPOSITION AND RUTHENIUM FILMS FORMED THEREBY," which claims priority from Korean Patent Application No. 1999-61337, filed December 23, 1999, and Korean Patent Application No. 2000-12056, filed March 10, 2000, the disclosures of which are incorporated by reference herein in their entireties.